

# Simulation and Analysis of 3D Spiral Inductor on High Insulating Substrate

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**Abstract:** Spiral inductors on semiconductor/insulator substrate play a crucial role in Radio Frequency Integrated Circuits (RFICs). For high frequency system circuitry, these components are realized using bond-wires or planar spirals. The Quality Factors (Q) of bond wires is higher than on-chip spirals, their use is constrained by the limited range of realizable inductances. The research presented here provides insight into some of the most pressing issues currently being addressed by the research community, and provides guidelines for designing these evolving heterogeneous Three Dimension (3D) systems. 3D spiral inductor integration is an evolving technology that will enhance the semiconductor roadmap for several generations. This dissertation provides insight into the 3-D inductor IC design process, with the goal of strengthening the design capabilities for 3-D integrated circuits and systems.

**Keywords:** Inductor, SiO<sub>2</sub>, Silicon, Glass, PEC.

## I. INTRODUCTION

Inductors and transformers are the fundamental building blocks of electronics, and they are found in every electronic device. Micro inductors and transformers are used in the field of radio frequency microelectromechanical systems (RF MEMS), micro actuators, and biosensors. Micro-inductors for power electronics is an emerging application in which inductors are used as energy storage elements for Switched Mode Power Supplies (SMPS). Miniaturization of SMPS has become the main focus for developing future generation power supplies known as Power Supply in package (Pwr SiP) and Power Supply on Chip (Pwr SoC). The Pwr SoC vision is to integrate all power electronics components on one chip. Higher integration lowers the cost and increases both efficiency and power density [1-8]. Therefore, one of the most important inductor requirements for Pwr SoC technology is the CMOS compatibility for on-chip integration. Other requirements are compact physical dimensions, a high-current capacity, and a high-quality factor for high efficiency. Switching at very high frequencies ranging from 30–300 MHz is one route toward Pwr SiP and Pwr SoC. In the VHF range, inductors with an air core or non-magnetic core are preferred, as suitable magnetic materials working at these frequencies are limited and the core implementation is very challenging [9-11].

The fundamental monolithic inductor is usually implemented as a spiral trace deposited on the passivation layer over a silicon substrate [12], as shown in Figure 1. The connection from the innermost turn can be taken out as a lead by an underpass or an air bridge. The design parameters are Number of turns (n), metal Width (w), Metal Spacing (s), Diameter of Outermost turn (d<sub>o</sub>), Diameter of Innermost turn (d<sub>i</sub>) and Arithmetic mean of inner and outer diameter (d<sub>avg</sub>).

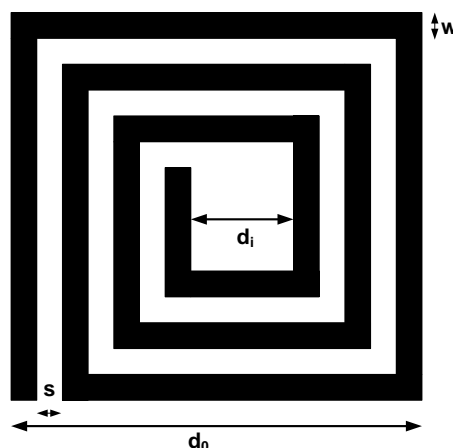


Fig. 1 Planar square spiral inductor.

The inductance [1] of the square planar coil is given by the equation.

$$L = \frac{9.375\mu_0 n^2 d_{avg}^2}{11d_0 - 7d_{avg}}$$

where  $\mu_0$  is the permeability of free space with a value of  $4\pi \cdot 10^{-7}$  H/m.

## II. SIMULATION PROCESS FLOW

The research work is formulated to simulate surficial spiral inductor and through substrate via based inductor. The proposed research simulation process flow chart is shown in Fig. 2.

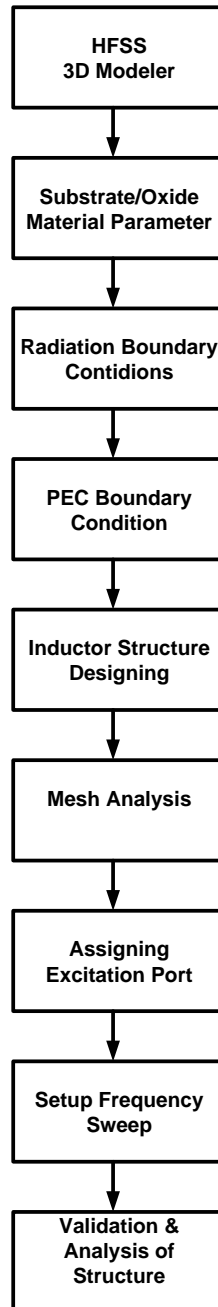


Fig. 2 Simulation process flow steps.

HFSS 3D modeler simulation tool is selected and active for the process. The first step is to select the appropriate substrate and oxide material for the designing of inductor. RF radiation is the main parameter which needed to be studied. Appropriate radiation boundary conditions are given to the design. The spiral of the inductors are made up of perfect

electric conductor, hence PEC boundary conditions must be given to the coil structure. Thus the complete geometry of the structure is coupled together. Meshing of the inductor structure is carried out. The mesh parameter of the structure will depend upon the system computing power. Next step is to assign the excitation port to the inductor. For the design lumped port excitation technique is taken. Lastly the frequency sweep is given to the simulation process; further the structure is validated and analyzed in frequency domain. S parameters, impedance, and quality factor the inductor will be optimized for RF applications.

### III. RESULTS AND DISCUSSION

The research work is carried out to simulate and analyse 3D spiral inductor. Highly insulating glass substrate is utilized having relative permittivity ( $\epsilon$ ) of 5.5 is used for simulation of 3D spiral inductor having 2.5 turn, width of  $15\mu\text{m}$  shown in Fig. 3. Frequency domain analysis of the designed spiral inductor was carried out in the frequency range of 0-20 GHz. S-parameters i.e.  $S_{11}$  &  $S_{21}$  were computed for the frequency 0-20 GHz shown in Fig. 4. It is observed from the graph that minimum insertion loss is observed at 19.30 GHz.

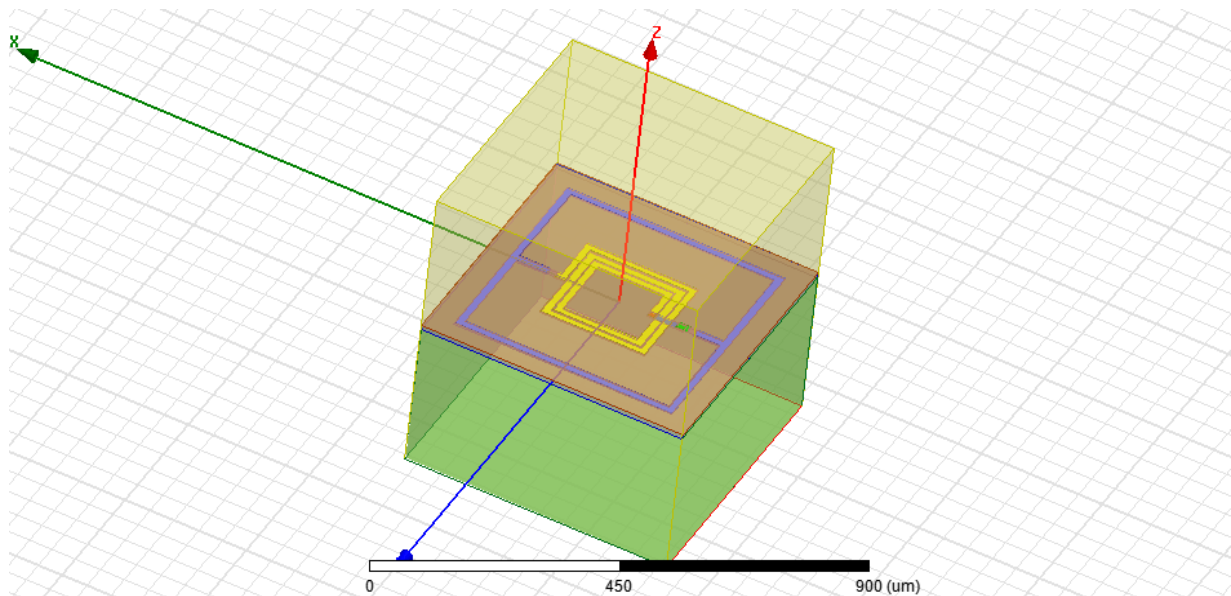


Fig. 3 Designed geometry of spiral inductor.

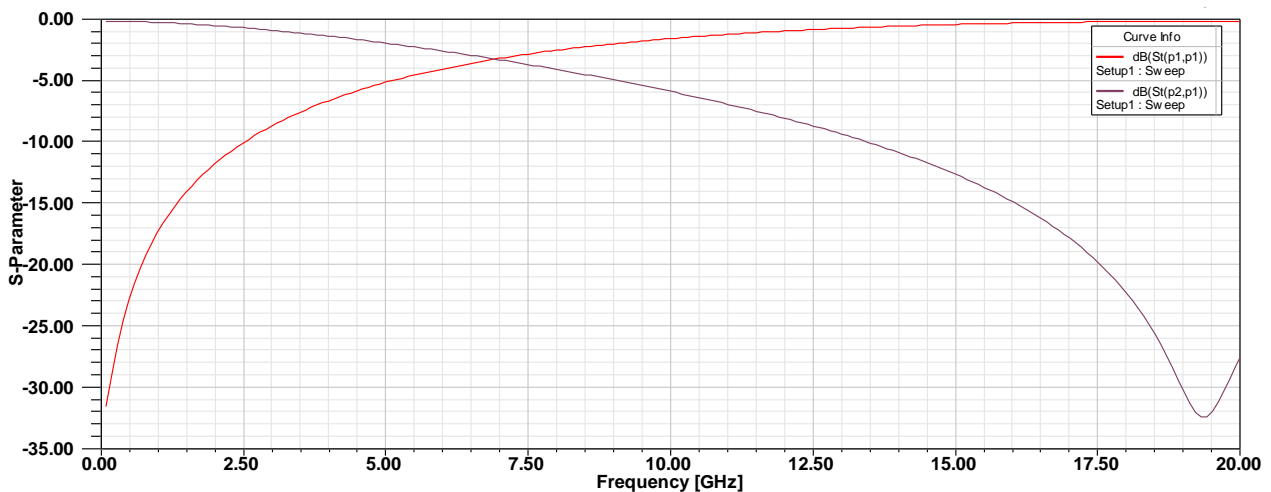


Fig. 4 S-parameter (insertion loss) of designed spiral inductor frequency ranging from 0-20 GHz.

Figure 5 shows the inductance of the designed 3D spiral inductor for the frequency ranging from 0-20 GHz. It is observed from the graph that maximum inductance of  $1.30\mu\text{H}$  is obtained at 16.20 GHz. Also, Q-factor is computed for the designed spiral inductor shown in Fig. 6. Both input port Q-factor i.e.  $Q_{11}$  and output port Q-factor i.e.  $Q_{22}$  of the inductor are computed and plotted.

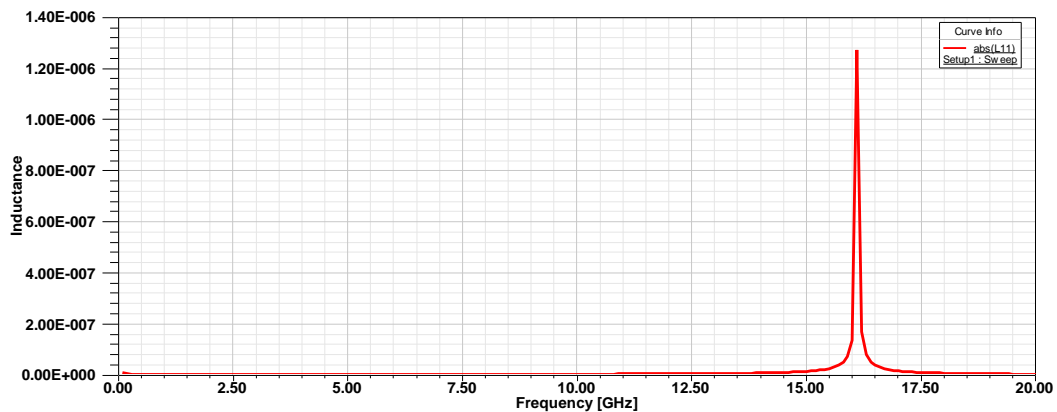


Fig. 5 Inductance of designed spiral inductor for frequency ranging from 0-20 GHz

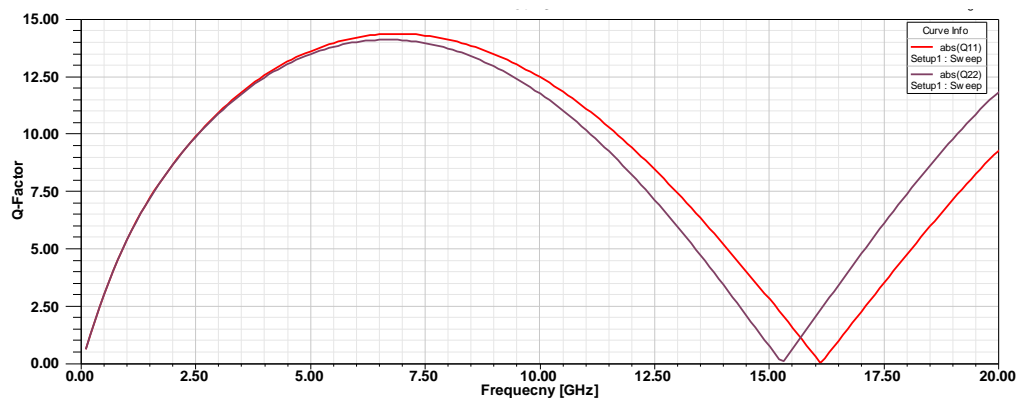


Fig. 6 Q-factor for designed inductor for frequency ranging from 0-20 GHz

## IV. CONCLUSION

In this research paper, rectangular spiral inductor is designed and simulated using FEM based platform. Spiral inductors are critical for filtering and tuning purposes in telecommunication field. It is important that the inductor model predict the Q-factor of the inductor, and the resonance accurately. The simulated spiral inductor shows  $1.30\mu\text{H}$  inductance at frequency at 16.20 GHz. The modelled device shows high Q-factor of 14.5. The result shows advantage of high insulating substrate over semiconductor substrate.

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